

IN THE CLAIMS

Please amend the claims as follows:

Claims 1-8 (Canceled).

Claim 9 (Currently Amended): A method of manufacturing an electron source device, comprising:

subjecting a metal substrate to electrolytic oxidation, thereby forming an oxide substrate having a number of small through holes, each of which opens to both surfaces of the metal substrate;

burying an electron-emitting material in the through holes of the oxide substrate;
forming a first electrode on one surface of the oxide substrate, said first electrode contacting the electron-emitting material; and

forming a second electrode on another surface of the oxide substrate, said second electrode insulated from the electron-emitting material.

Claim 10 (Original): The method of manufacturing an electron source device, according to claim 9, wherein an electrolysis voltage is controlled, in the electrolytic oxidation, to control the diameter of the small through holes.

Claim 11 (Original): The method of manufacturing an electron source device, according to claim 9, wherein an electrolysis time is controlled, in the electrolytic oxidation, to control the diameter of the small through holes.

Claim 12 (Original): The method of manufacturing an electron source device, according to claim 9, wherein the electron-emitting material is buried in the through holes by

introducing an organic substance into the through holes and then baking the organic substance to carbonize the substance.

Claim 13 (Currently Amended): The method of manufacturing an electron source device, according to claim 12, wherein the oxide substrate is coated with ~~[[an]]~~ a mold release agent before the organic substance is introduced.

Claim 14 (Original): The method of manufacturing an electron source device, according to claim 9, wherein the electron-emitting material is buried in the through holes by vapor-depositing an organic substance in the through holes.

Claims 15-18 (Canceled).

Claim 19 (New): A method of manufacturing an electron source device of a flat display apparatus which comprises a first substrate and a second substrate arranged opposite to each other; phosphor layers provided on an inner surface of the first substrate, and an electron source device provided between the first and second substrates, configured to excite the phosphor layers, the method comprising:

subjecting to electrolytic oxidation a metal substrate having a first surface opposing the second substrate and a second surface contacting the phosphor layers, thereby forming an oxide substrate having a number of small through holes, each of which includes a first opening open to the first surface and a second opening open to the second surface;

burying a single kind of electron-emitting material in the through holes of the oxide substrate from the first openings to regions closed to the second openings;

forming a first electrode on one surface of the oxide substrate, said first electrode contacting the electrode on one surface of the oxide substrate, said first electrode contacting the electron-emitting material; and

forming a second electrode on another surface of the oxide substrate, said second electrode insulated from the electron-emitting material.